

*“Interpretation of TOF-SIMS depth profiles from ultrashallow high- $k$  dielectric stacks assisted by hybrid collisional computer simulation”.* Ignatova VA, Möller W, Conard T, Vandervorst W, Gijbels R, Applied physics A : materials science & processing **81**, 71 (2005). <http://doi.org/10.1007/s00339-005-3239-8>